L Number	Hits		DB	Time stamp
1	98	(((resist or photoresist or	USPAT;	2004/08/14 10:19
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	
}		(Ne or neon)) with (flow or flowrate or	EPO; JPO;	
		rate or sccm or slm))) not ((430/328.ccls.	IBM_TDB	
		not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))		
		not (((resist or photoresist or		
		photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
1		((430/328.ccls. not 430/313.cor.) and ((Ar		1
		or argon or inert) with (flow or flowrate		
		or rate))))		
2	3	,,,,,=================================	USPAT;	2004/08/14 10:20
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	EPO; JPO;	
		cur\$3 or harden\$3))) and etch\$3) and (Ne)	IBM_TDB	
3	1	(((((resist or photoresist or	USPAT;	2004/08/14 10:24
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	2001/00/14 10.24
,		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM TDB	
	_	cur\$3 or harden\$3))) and etch\$3) and neon		
4	2	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/08/14 10:25
Ì		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same	EPO; JPO;	
		(flow or flowrate))	IBM_TDB	
5	21	430/313.cor. and 430/328.cxr. not (etch\$3	USPAT;	2004/08/14 10:28
		with chamber)	US-PGPUB;	2004/08/14 10:28
		·	EPO; JPO;	
			IBM TDB	
6	17	((((post adj (expos\$ or develop\$4)) adj20	USPAT;	2004/08/14 10:30
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	
		or silicone) with (polymer\$7 or	EPO; JPO;	1
İ		<pre>photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or</pre>	IBM_TDB	
		substrate))) and etch\$3		
7	3	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/08/14 10:31
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2004/08/14 10:31
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	1
		photoresist or resist))) and ((Ar or argon	IBM TDB	
		or inert) with (flow or flowrate or rate))	_	
8	15	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/08/14 10:32
		or argon or inert) with (flow or flowrate	US-PGPUB;	
		or rate))	EPO; JPO;	
9	12	((430/328.ccls. not 430/313.cor.) and ((Ar	IBM_TDB USPAT;	2004/09/14 10:20
		or argon or inert) same (flow or flowrate	US-PGPUB;	2004/08/14 10:32
	ĺ	or rate))) not ((430/328.ccls. not	EPO; JPO;	
		430/313.cor.) and ((Ar or argon or inert)	IBM TDB	
	1	with (flow or flowrate or rate)))		
10	2	((430/328.ccls. not 430/313.cor.) and	USPAT;	2004/08/14 10:33
ļ		(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	
ĺ		(flow or flowrate or rate or sccm or	EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM_TDB	
İ		430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))		
11	26	((resist or photoresist or photopolymer\$7)	USPAT;	2004/08/14 10:33
		and (((Ar or argon) and (Ne or neon)) with	US-PGPUB;	2004/00/14 10:33
		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not	IBM TDB	
		430/313.cor.) and ((Ar or argon or inert)		
		with (flow or flowrate or rate)))		

12 98	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:34
13 646		USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:36
14 3	<pre>((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon</pre>	USPAT; US-PGPUB; EPO; JPO;	2004/08/14 10:37
15 1	photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:37
16 0	<pre>cur\$3 or harden\$3))) and etch\$3) and neon (((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:38
17 135	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO;	2004/08/14 10:38
18 7	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:39

19	89			
	89	((dreravroice or a., mrem (NC)) and	USPAT;	2004/08/14 10:39
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
İ		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
0.0		photoresist or resist))	IBM TDB	
20	4	1 - 07 0 20 : COI: and 100 / O 20 : CMI: and (CECTION	USPAT;	2004/08/14 10:40
		with chamber)	US-PGPUB;	
			EPO; JPO;	
			IBM TDB	
21	5	250/504R-504H.ccls. and (neon or Ne) with	USPAT:	2004/08/14 10:41
		(ultraviolet or uv)	US-PGPUB;	2001,00,14 10.41
			EPO; JPO;	
			IBM TDB	
22	19	430/328.ccls. and (uv or ultraviolet or	USPAT:	2004/08/14 10:42
		ultra adj violet) same (temperature or	US-PGPUB;	2004/00/14 10.42
		\$4"degree") same plasma	EPO; JPO;	!
			IBM TDB	
23	156	430/328.ccls. and (uv or ultraviolet or	USPAT;	2004/08/14 10:45
		ultra adj violet) same (temperature or	US-PGPUB;	2004/08/14 10:45
		\$4"degree") not plasma	EPO; JPO;	J
		r = ====== / Hot prasma	IBM TDB	
24	4.3	430/313.ccls. and (uv or ultraviolet or	USPAT:	2004/20/14 14 25
		ultra adj violet) same (\$4"degree") same		2004/08/14 11:03
	}	plasma not 430/328.ccls.	US-PGPUB;	
		P103ma 1100 430/320.0018.	EPO; JPO;	
25	371	(resist or photoresist) same (uv or	IBM_TDB	
2.5] 3/4	ultraviolet or ultra add	USPAT;	2004/08/14 11:04
	[ultraviolet or ultra adj violet) same	US-PGPUB;	
	1	(\$4"degree") same plasma	EPO; JPO;	1
26	25	250/504D 504H1	IBM_TDB	
20	25	250/504R-504H.ccls. and plasma and (uv or	USPAT;	2004/08/14 11:05
		ultraviolet or ultra adj violet) same	US-PGPUB;	
İ	į l	(\$4"degree")	EPO; JPO;	
	L		IBM TDB	